

BEST AVAILABLE COPY

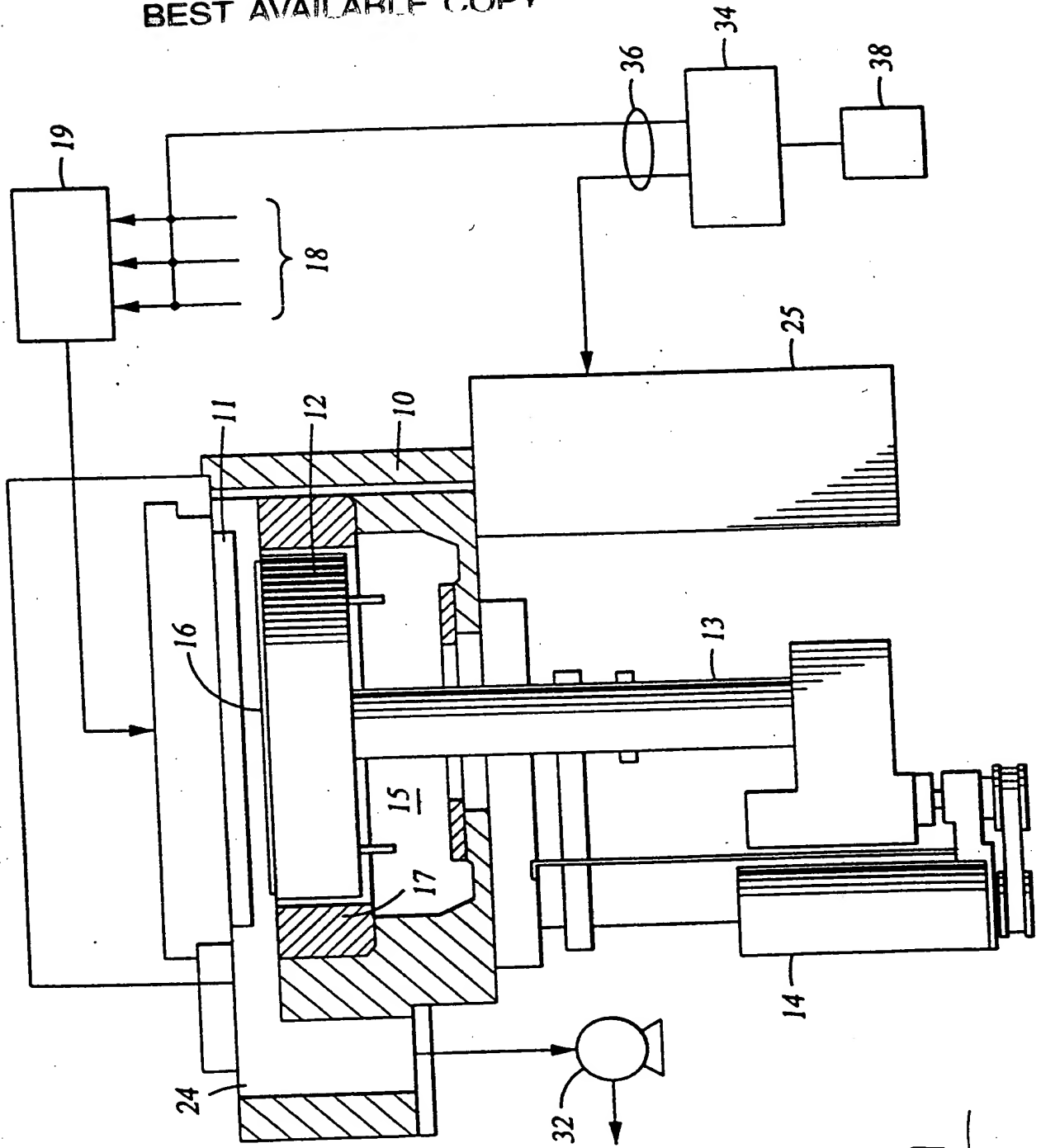


Fig. 1

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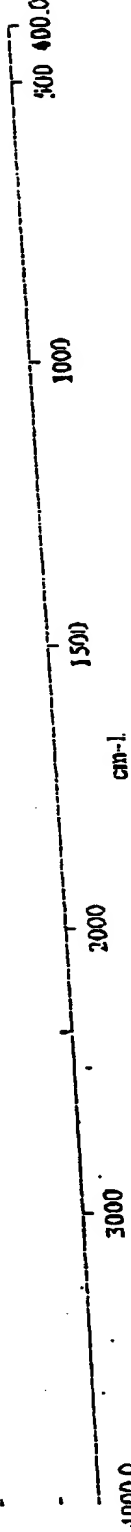
① FTIR for As Deposited
 Films (SiC) ~~After~~
 He plasma treatment
 ③ and after O₂ plasma exposure

Refractive Index = 1.90

SiC
 Si-O Si-CH₃ ↑
 ↑

Refractive index = 1.80

① FTIR for After N₂O plasma treatment
 ② FTIR after O₂ plasma exposure



c:\pel_data\spectra\ing10_80d.sp - before O₂ etch
 c:\pel_data\spectra\ing10_80d.sp - after etching
 c:\pel_data\spectra\ing10_80d.sp - after O₂ etching

Fig. 2

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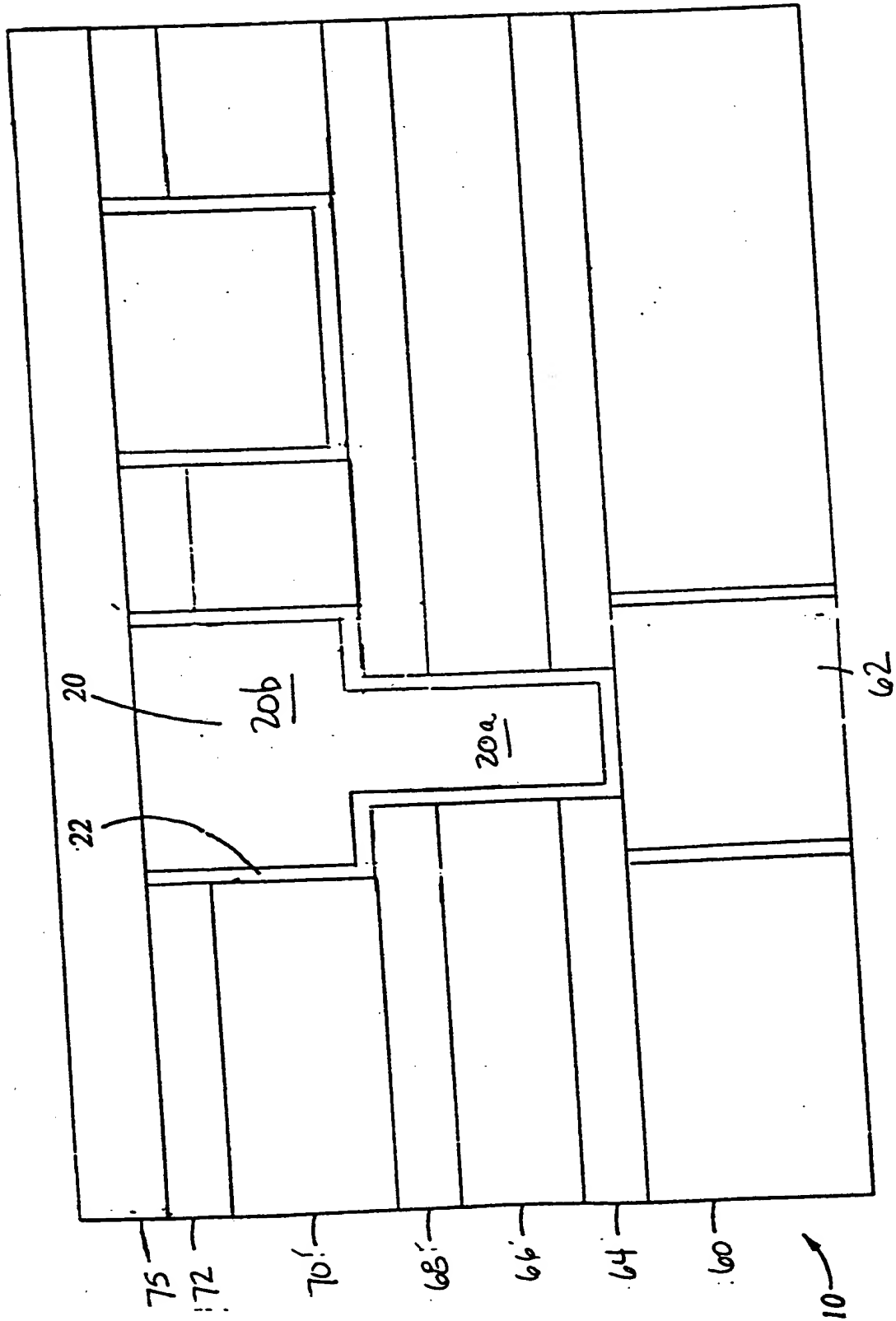


Fig. 3